

**Docket No: H1542****Serial No. 10/727,393****In the Specification**

Please amend the paragraphs at page 18, lines 7-26, to read as follows:

As noted above, in the embodiment depicted in Fig. 7, the diffuser **[[24]] 54** is disposed between the illumination source 20 and the mask or reticle 30 on which the light-reflecting areas 14, 14' are formed, but the light 22 is reflected from the diffuser **54** rather than being transmitted, as through the diffuser 24 **[[as]]** in the embodiments of Figs. 3-6. Although it is reflective rather than transmissive, this feature, including oscillation of the diffuser **[[24]] 54** as needed, allows use of the diffuser **[[24]] 54** to remove effects from the illumination source aperture uniformity or non-uniformity from the determination of the reflection lens pupil transmission distribution. Use of the apparatus 100, 200, 300 or 400, as well as the various equivalent embodiments disclosed herein, without the diffuser 24 present, allows determination of the pupil distribution with effects from both the illumination source aperture and the reflection lens. Thus, the present invention provides a device and method for separating the effects of these variables affecting the pupil image, and thereby provides for control and adjustment of the photolithographic process to a degree greater than in the prior art.

In carrying out the method of the present invention with the embodiment of Fig. 7, in one embodiment, when the diffuser **[[24]] 54** is removed, it may be replaced by a reflective non-diffusive element or, in another embodiment, when the diffuser **[[24]] 54** is removed, the illumination source 20 may be realigned to that the light 22 is directed to the mask 30 without reflection.